

Examiner-Initiated Interview Summary	Application No.	Applicant(s)
	10/824,798	SHINRIKI ET AL.
	Examiner Rudy Zervigon	Art Unit 1763

All Participants:

(1) Rudy Zervigon.

Status of Application: _____

(3) _____.

(2) Katsuhiro Arai.

(4) _____.

Date of Interview: 10 June 2007

Time: 07:48

Type of Interview:

- Telephonic
 Video Conference
 Personal (Copy given to: Applicant Applicant's representative)

Exhibit Shown or Demonstrated: Yes No

If Yes, provide a brief description:

Part I.

Rejection(s) discussed:

None

Claims discussed:

1, 30

Prior art documents discussed:

None

Part II.

SUBSTANCE OF INTERVIEW DESCRIBING THE GENERAL NATURE OF WHAT WAS DISCUSSED:

See Continuation Sheet

Part III.

- It is not necessary for applicant to provide a separate record of the substance of the interview, since the interview directly resulted in the allowance of the application. The examiner will provide a written summary of the substance of the interview in the Notice of Allowability.
 It is not necessary for applicant to provide a separate record of the substance of the interview, since the interview did not result in resolution of all issues. A brief summary by the examiner appears in Part II above.

(Examiner/SPE Signature)

(Applicant/Applicant's Representative Signature – if appropriate)

Continuation of Substance of Interview including description of the general nature of what was discussed: The Examiner left a message and sent a fax transmission to Mr. Arai's assistant (see attachment) requesting authorization for the Examiner's amendment to bring the case into condition for allowance. Mr. Arai returned the Examiner's communication in the morning of June 10th authorizing the amendment. The Examiner notes that a closer inspection of claims 10 and 11 required an additional minor amendment to maintain antecedence with independent claim 1..



Patent Technology Centers

Facsimile Transmission

To:	Name:	Katsuhiro Arai
	Company:	
	Fax Number:	9497609502
	Voice Phone:	
From:	Name:	Examiner Rudy Zervigon
	Official Fax Number:	(571) 273-8300
	Official After Final Fax Number:	(571) 273-8300
	Voice Phone:	571.272.1442

37 C.F.R. 1.6 sets forth the types of correspondence that can be communicated to the Patent and Trademark Office via facsimile transmissions. Applicants are advised to use the certificate of facsimile transmission procedures when submitting a reply to a non-final or final Office action by facsimile (37 CFR 1.8(a)).

Fax Notes:

Hello Mr. Arai, I spoke to your helpful assistant this afternoon. Please consider the fax transmission of the proposed Examiner's amendment to the claims for immediate consideration and allowance of the claims. I need a response by Monday latest. The sooner a favorable response is in will permit me to prepare the amendment for issuing the application.

Rudy Zervigon
Primary Examiner, Art Unit 1763
Remsen 7A69

Date and time of transmission: Thursday, June 07, 2007 4:16:56 PM
Number of pages including this cover sheet: 03

PROPOSED EXAMINER'S AMENDMENT

1. An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

Authorization for this examiner's amendment was given in a telephone interview with Katsuhiro Arai on NOT YET AUTHORIZED.

The application has been amended as follows:

1 (currently amended): A gas-feeding apparatus ~~configured to be~~ connected to an evacuable reaction chamber provided with a support for placing a substrate thereon, a gas-distribution head for introducing gases into the chamber through a head surface, comprising: a first plate having exclusively a first flow channel for discharging a first gas therein through the first flow channel and the head surface toward the support; and a second plate constituting the head surface and an exhaust path and disposed under the first plate, said second plate having both the first flow channel and a second flow channel which is for discharging a second gas through the second flow channel and the head surface toward the support, wherein there is no gas-mixing between the first flow channel and the second flow channel, ~~at least one of which flow channels said exhaust path~~ is coupled to an exhaust system for purging therefrom a gas present in the corresponding flow channel without passing through the head surface, said first and second plates being stratified parallel to each other in a direction perpendicular to their axial direction and being overlapped as viewed in the axial direction, said second plate being closer to the head surface than is the first plate.

Claim 30 (currently amended): A gas-feeding apparatus ~~adapted to be~~ connected to an evacuable reaction chamber for atomic layer growth processing, comprising: a distribution plate; a first plate having exclusively first bores through which a first gas passes, wherein a first section is formed between the distribution plate and the first plate, wherein the first gas is introduced into the first section and passes through the first bores; and a second plate having second bores through which a second gas passes, wherein a second section is formed between the first plate and the second plate, wherein the second gas is introduced into the second section and passes through the second bores, said second plate further having third bores through which the first gas passes, wherein there is no gas communication between the third bores and the second bores, but there is gas communication between the third bores and the first bores, wherein the second plate is disposed above the support, the first plate is disposed above the second plate, and the distribution plate is disposed above the first plate, the first plate and the second plate are overlapped as viewed in their axial direction where the second plate has both the second bores

and the third bores and the first plate has the first bores only, either both and at least one of the first section or and the second section is coupled to an exhaust system or the second section is coupled to an exhaust system exclusively which discharges the gas in the corresponding section without passing through the corresponding bores.